

Notice of References Cited		Application/Control No. 10/583,570	Applicant(s)/Patent Under Reexamination DESIMONE ET AL.	
		Examiner JESSICA WORSHAM	Art Unit 1615	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2004/0115239 A1	06-2004	Shastri et al.	424/423
*	B	US-6,645,432	11-2003	Anderson et al.	422/502
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Rothschild, M.; Bloomstein, T.M.; Fedynyshyn, T.H.; Liberman, V.; Mowers, W.; Sinta, R.; Switkes, M.; Grenville, A.; Orvek, K. Fluorine-an enabler in advanced photolithography. Journal of Fluorine Chemistry, Vol. 122, 2003, pages 3-10.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.06(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.